

## IN-LINE DEPOSITION PROCESSES FOR CIRCUIT FABRICATION

### ABSTRACT

5           In one embodiment, the invention is directed to aperture mask deposition  
techniques using aperture mask patterns formed in one or more elongated webs of flexible  
film. The techniques involve sequentially depositing material through mask patterns  
formed in the film to define layers, or portions of layers, of the circuit. A deposition  
substrate can also be formed from an elongated web, and the deposition substrate web can  
10 be fed through a series of deposition stations. Each deposition station may have an  
elongated web formed with aperture mask patterns. The elongated web of mask patterns  
feeds in a direction perpendicular to the deposition substrate web. In this manner, the  
circuit creation process can be performed in-line. Moreover, the process can be automated  
to reduce human error and increase throughput.  
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